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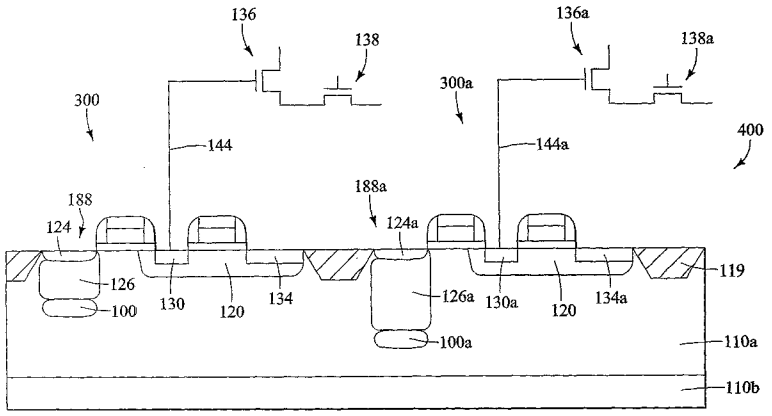
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(54) **Title:** COLOR PIXELS WITH ANTI-BLOOMING ISOLATION AND METHOD OF FORMATION



(57) **Abstract:** Implant regions of a first conductivity type (100) are formed under at least a portion of a first pixel sensor cell (188) and of a second pixel cell (188a) to limit the depth of the photodiode collection/depletion region and limit the pixel's color response. To further reduce cross-talk between adjacent pixels and to decrease blooming, an anti-blooming isolation region (200) of a second conductivity type is formed in the substrate and below the stop implant regions of the first conductivity type.

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